

09/867,662  
Art Unit: 1762

**Amendments to the Specification**

Please amend the numbered paragraphs as follows:

-- [0010] In its broad aspect the present invention provides a method of depositing optical quality films by PECVD (Plasma Enhanced Chemical Vapour Deposition), comprising depositing an optical film by PECVD (Plasma Enhanced Chemical Vapour Deposition) in the presence of reactive gases; and controlling the flow rate of at least one of said reactive gases to minimize unwanted absorption peaks in the deposited film achieve the desired difference in refractive indices ( $\Delta n$ ). --